

REMARKS

Claims 1-16 and 29-38 are pending in this application. By this Amendment, claim 1 is amended. No new matter is added.

I. CLAIM AMENDMENT

This amendment does not narrow claim 1. On the contrary, claim 1 is broadened by the inclusion of the phrase "at least the first portion." Further, claim 1 is clarified and broadened by reciting that only a second portion of the first protective layer is removed to expose a second portion of the substrate, without necessarily removing a portion of the second protective layer. Claim 1 is also clarified by reciting the inherent features of exposing first and second portions of the substrate by removing portions of the first protective layer.

II. ELECTION

In reply to the August 12, 2003 Restriction Requirement, Applicants provisionally elect Group I, claims 1-16 and 29-38 drawn to a method for integrating a plurality of heterogeneous circuit devices.

The Office Action states that the basis for the restriction requirement is that the product can be made by a another and materially different process, "such as, removing a first portion of the protective layer to implant the high voltage well and then removing a second portion of the protective layer to implant the low voltage well, without forming and removing a second protective layer." Applicants respectfully disagree.

Claim 1, as amended, does not recite that any portion of the second protective layer is removed. Thus, this basis for the restriction requirement is rendered moot. Moreover, the Office Action is incorrect in stating that the low voltage well can be implanted without forming a second protective layer. The second protective is formed over at least the high voltage well to protect the high voltage well from the second ion implantation. Otherwise, the high voltage well will be exposed to the second ion implantation. Therefore, it is respectfully submitted that the basis for restriction stated in the Office Action is improper.

It is also respectfully submitted that the subject matter of all claims 1-46 is sufficiently related that a thorough search for the subject matter of any one Group of claims would encompass a search for the subject matter of the remaining claims. Thus, it is respectfully submitted that the search and examination of the entire application could be made without serious burden. See MPEP §803 in which it is stated that "if the search and examination of an entire application can be made without serious burden, the examiner must examine it on the merits, even though it includes claims to independent or distinct inventions" (emphasis added). It is respectfully submitted that this policy should apply in the present application in order to avoid unnecessary delay and expense to Applicants and duplicative examination by the Patent Office.

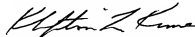
Thus, withdrawal of the Restriction Requirement is respectfully requested.

III. CONCLUSION

In view of the foregoing, it is respectfully submitted that this application is in condition for allowance. Favorable reconsideration and prompt allowance of claims 1-46 are earnestly solicited.

Should the Examiner believe that anything further would be desirable in order to place this application in even better condition for allowance, the Examiner is invited to contact the undersigned at the telephone number set forth below.

Respectfully submitted,



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